# Jaroslav VlÄek

List of Publications by Year
in descending order



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|---|---|---|---|
| 130 papers | 4,616 citations | 94269 37 h-index | 118652 62 g-index |
| 130 all docs | 130 docs citations | 130 times ranked | 2649 citing authors |

| # | Article | IF | Citations |
|---|---|---|---|
| 1 | Reactive magnetron sputtering of thin films: present status and trends. Thin Solid Films, 2005, 475, 208-218. | 0.8 | 329 |
| 2 | Collisional-radiative model for an argon glow discharge. Journal of Applied Physics, 1998, 84, 121-136. | 1.1 | 223 |
| 3 | A collisional-radiative model applicable to argon discharges over a wide range of conditions. I. Formulation and basic data. Journal Physics D: Applied Physics, 1989, 22, 623-631. | 1.3 | 215 |
| 4 | Magnetron sputtering of hard nanocomposite coatings and their properties. Surface and Coatings Technology, 2001, 142-144, 557-566. | 2.2 | 205 |
| 5 | Microstructure and properties of nanocomposite Tiâ€"Bâ€"N and Tiâ€"Bâ€"C coatings. Surface and Coatings Technology, 1999, 120-121, 405-411. | 2.2 | 170 |
| 6 | Mechanical and optical properties of hard SiCN coatings prepared by PECVD. Thin Solid Films, 2004, 447-448, 201-207. | 0.8 | 145 |
| 7 | Magnetron sputtering of films with controlled texture and grain size. Materials Chemistry and Physics, 1998, 54, 116-122. | 2.0 | 111 |
| 8 | Pulsed dc Magnetron Discharges and their Utilization in Plasma Surface Engineering. Contributions To Plasma Physics, 2004, 44, 426-436. | 0.5 | 110 |
| 9 | Reactive magnetron sputtering of hard Siâ€"Bâ€"Câ€"N films with a high-temperature oxidation resistance. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2005, 23, 1513-1522. | 0.9 | 76 |
| 10 | Electron energy distributions and plasma parameters in high-power pulsed magnetron sputtering discharges. Plasma Sources Science and Technology, 2009, 18, 025008. | 1.3 | 76 |
| 11 | High-power pulsed sputtering using a magnetron with enhanced plasma confinement. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 42-47. | 0.9 | 75 |
| 12 | Process stabilization and a significant enhancement of the deposition rate in reactive high-power impulse magnetron sputtering of ZrO2 and Ta2O5 films. Surface and Coatings Technology, 2013, 236, 550-556. | 2.2 | 72 |
| 13 | Pulsed dc magnetron discharge for high-rate sputtering of thin films. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2001, 19, 420-424. | 0.9 | 71 |
| 14 | Reactive magnetron sputtering of TiOx films. Surface and Coatings Technology, 2005, 193, 107-111. | 2.2 | 69 |
| 15 | Hard amorphous nanocomposite coatings with oxidation resistance above 1000Â°C. Advances in Applied Ceramics, 2008, 107, 148-154. | 0.6 | 68 |
| 16 | Tribological study of CNx films prepared by reactive d.c. magnetron sputtering. Wear, 1997, 213, 80-89. | 1.5 | 66 |
| 17 | A phenomenological equilibrium model applicable to high-power pulsed magnetron sputtering. Plasma Sources Science and Technology, 2010, 19, 065010. | 1.3 | 66 |
| 18 | Reactive magnetron sputtering of CNx films: Ion bombardment effects and process characterization using optical emission spectroscopy. Journal of Applied Physics, 1999, 86, 3646-3654. | 1.1 | 61 |

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| 19 | Ion flux characteristics in high-power pulsed magnetron sputtering discharges. Europhysics Letters, 2007, 77, 45002. | 0.7 | 61 |
| 20 | High-temperature oxidation of TiN/CrN multilayers reactively sputtered at low temperatures. Surface and Coatings Technology, 1998, 98, 1497-1502. | 2.2 | 59 |
| 21 | Highly ionized fluxes of sputtered titanium atoms in high-power pulsed magnetron discharges. Plasma Sources Science and Technology, 2008, 17, 025010. | 1.3 | 58 |
| 22 | Benefits of the controlled reactive high-power impulse magnetron sputtering of stoichiometric ZrO2 films. Vacuum, 2015, 114, 131-141. | 1.6 | 56 |
| 23 | Influence of substrate bias voltage on structure and properties of hard Siâ€“Bâ€“Câ€“N films prepared by reactive magnetron sputtering. Diamond and Related Materials, 2007, 16, 29-36. | 1.8 | 55 |
| 24 | Structure-hardness relations in sputtered Tiâ€“Alâ€“Vâ€“N films. Thin Solid Films, 2003, 444, 189-198. | 0.8 | 54 |
| 25 | Magnetron sputtering of alloy and alloy-based films. Thin Solid Films, 1999, 343-344, 47-50. | 0.8 | 53 |
| 26 | Modeling of glow discharge optical emission spectrometry: Calculation of the argon atomic optical emission spectrum. Spectrochimica Acta, Part B: Atomic Spectroscopy, 1998, 53, 1517-1526. | 1.5 | 50 |
| 27 | A perspective of magnetron sputtering in surface engineering. Surface and Coatings Technology, 1999, 112, 162-169. | 2.2 | 50 |
| 28 | High-rate reactive high-power impulse magnetron sputtering of hard and optically transparent HfO 2 films. Surface and Coatings Technology, 2016, 290, 58-64. | 2.2 | 49 |
| 29 | Influence of nitrogenâ€“argon gas mixtures on reactive magnetron sputtering of hard Siâ€“Câ€“N films. Surface and Coatings Technology, 2002, 160, 74-81. | 2.2 | 46 |
| 30 | Absolute OH and O radical densities in effluent of a He/H<sub>2</sub>O micro-scaled atmospheric pressure plasma jet. Plasma Sources Science and Technology, 2016, 25, 045013. | 1.3 | 46 |
| 31 | Significant improvement of the performance of ZrO2/V1-W O2/ZrO2 thermochromic coatings by utilizing a second-order interference. Solar Energy Materials and Solar Cells, 2019, 191, 365-371. | 3.0 | 46 |
| 32 | A collisional-radiative model applicable to argon discharges over a wide range of conditions. II. Application to low-pressure, hollow-cathode arc and low-pressure glow discharges. Journal Physics D: Applied Physics, 1989, 22, 632-643. | 1.3 | 45 |
| 33 | Effect of ion bombardment on properties of hard reactively sputtered Ti(Fe)Nx films. Surface and Coatings Technology, 2004, 177-178, 289-298. | 2.2 | 43 |
| 34 | Effect of the gas mixture composition on high-temperature behavior of magnetron sputtered Siâ€“Bâ€“Câ€“N coatings. Surface and Coatings Technology, 2008, 203, 466-469. | 2.2 | 42 |
| 35 | Thermal stability of magnetron sputtered Siâ€“Bâ€“Câ€“N materials at temperatures up to 1700Â°C. Thin Solid Films, 2010, 519, 306-311. | 0.8 | 41 |
| 36 | Comparison of hydrophilic properties of TiO2 thin films prepared by solâ€“gel method and reactive magnetron sputtering system. Thin Solid Films, 2011, 519, 6944-6950. | 0.8 | 41 |

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| 37 | Controlled reactive HiPIMSâ€"effective technique for low-temperature (300 Â°C) synthesis of VO<sub>2</sub>films with semiconductor-to-metal transition. Journal Physics D: Applied Physics, 2017, 50, 38LT01. | 1.3 | 38 |
| 38 | Recent progress in plasma nitriding. Vacuum, 2000, 59, 940-951. | 1.6 | 37 |
| 39 | Effect of nitrogen content on electronic structure and properties of SiBCN materials. Acta Materialia, 2011, 59, 2341-2349. | 3.8 | 36 |
| 40 | Microstructure characterization of high-temperature, oxidation-resistant Si-B-C-N films. Thin Solid Films, 2013, 542, 167-173. | 0.8 | 35 |
| 41 | Reactive magnetron sputtering of Siâ€"Câ€"N films with controlled mechanical and optical properties. Diamond and Related Materials, 2003, 12, 1287-1294. | 1.8 | 34 |
| 42 | Effect of B and the Si/C ratio on high-temperature stability of Siâ€"Bâ€"Câ€"N materials. Europhysics Letters, 2006, 76, 512-518. | 0.7 | 34 |
| 43 | A parametric model for reactive high-power impulse magnetron sputtering of films. Journal Physics D: Applied Physics, 2016, 49, 055202. | 1.3 | 34 |
| 44 | Characterization of thermochromic VO2 (prepared at 250 Â°C) in a wide temperature range by spectroscopic ellipsometry. Applied Surface Science, 2017, 421, 529-534. | 3.1 | 34 |
| 45 | Measurement of hardness of superhard films by microindentation. Materials Science & Engineering A: Structural Materials: Properties, Microstructure and Processing, 2003, 340, 281-285. | 2.6 | 33 |
| 46 | Emission spectroscopy of the plasma in the cathode region of N2-H2abnormal glow discharges for steel surface nitriding. Journal Physics D: Applied Physics, 1993, 26, 585-589. | 1.3 | 29 |
| 47 | Formation of high temperature phases in sputter deposited Tiâ€based films below 100â€‰Â°C. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 2247-2250. | 0.9 | 29 |
| 48 | Influence of substrate bias voltage on the properties of CNx films prepared by reactive magnetron sputtering. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1999, 17, 899-908. | 0.9 | 29 |
| 49 | High-rate reactive high-power impulse magnetron sputtering of Taâ€"Oâ€"N films with tunable composition and properties. Thin Solid Films, 2014, 566, 70-77. | 0.8 | 29 |
| 50 | High-performance thermochromic VO2-based coatings with a low transition temperature deposited on glass by a scalable technique. Scientific Reports, 2020, 10, 11107. | 1.6 | 29 |
| 51 | Langmuir probe measurements of plasma parameters in a planar magnetron with additional plasma confinement. Vacuum, 1999, 55, 165-170. | 1.6 | 28 |
| 52 | Superior high-temperature oxidation resistance of magnetron sputtered Hfâ€"Bâ€"Siâ€"Câ€"N film. Ceramics International, 2016, 42, 4853-4859. | 2.3 | 28 |
| 53 | Magnetron sputtered Siâ€"Bâ€"Câ€"N films with high oxidation resistance and thermal stability in air at temperatures above 1500â€‰Â°C. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2008, 26, 1101-1108. | 0.9 | 27 |
| 54 | High-temperature stability of the mechanical and optical properties of Siâ€"Bâ€"Câ€"N films prepared by magnetron sputtering. Thin Solid Films, 2009, 518, 174-179. | 0.8 | 27 |

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| 55 | Ion flux characteristics and efficiency of the deposition processes in high power impulse magnetron sputtering of zirconium. Journal of Applied Physics, 2010, 108, . | 1.1 | 26 |
| 56 | Properties of thermochromic VO2 films prepared by HiPIMS onto unbiased amorphous glass substrates at a low temperature of 300â€¯Â°C. Thin Solid Films, 2018, 660, 463-470. | 0.8 | 26 |
| 57 | Ab initiosimulations of nitrogen evolution in quenchedCNxand SiBCN amorphous materials. Physical Review B, 2005, 72, . | 1.1 | 25 |
| 58 | A study of the microstructure evolution of hard Zrâ€“Bâ€“Câ€“N films by high-resolution transmission electron microscopy. Acta Materialia, 2014, 77, 212-222. | 3.8 | 25 |
| 59 | Microstructure of hard and optically transparent HfO2 films prepared by high-power impulse magnetron sputtering with a pulsed oxygen flow control. Thin Solid Films, 2016, 619, 239-249. | 0.8 | 25 |
| 60 | A comparison of internal plasma parameters in a conventional planar magnetron and a magnetron with additional plasma confinement. Plasma Sources Science and Technology, 1997, 6, 46-52. | 1.3 | 24 |
| 61 | Improved performance of thermochromic VO2/SiO2 coatings prepared by low-temperature pulsed reactive magnetron sputtering: Prediction and experimental verification. Journal of Alloys and Compounds, 2018, 767, 46-51. | 2.8 | 24 |
| 62 | Mechanical and optical properties of quaternary Siâ€“Bâ€“Câ€“N films prepared by reactive magnetron sputtering. Thin Solid Films, 2008, 516, 7286-7293. | 0.8 | 23 |
| 63 | Hard nanocrystalline Zrâ€“Bâ€“Câ€“N films with high electrical conductivity prepared by pulsed magnetron sputtering. Surface and Coatings Technology, 2013, 215, 186-191. | 2.2 | 23 |
| 64 | A collisional-radiative model applicable to argon discharge over a wide range of conditions. IV. Application to inductively coupled plasmas. Journal Physics D: Applied Physics, 1991, 24, 309-317. | 1.3 | 22 |
| 65 | Morphology and Microstructure of Hard and Superhard Zrâ€“Cuâ€“N Nanocomposite Coatings. Japanese Journal of Applied Physics, 2002, 41, 6529-6533. | 0.8 | 22 |
| 66 | Pulsed reactive magnetron sputtering of high-temperature Siâ€“Bâ€“Câ€“N films with high optical transparency. Surface and Coatings Technology, 2013, 226, 34-39. | 2.2 | 22 |
| 67 | Structure and properties of Hf-O-N films prepared by high-rate reactive HiPIMS with smoothly controlled composition. Ceramics International, 2017, 43, 5661-5667. | 2.3 | 22 |
| 68 | The effect of nitrogen on analytical glow discharges studied by high resolution Fourier transform spectroscopy. Journal of Analytical Atomic Spectrometry, 2003, 18, 549-556. | 1.6 | 21 |
| 69 | Bonding statistics and electronic structure of novel Siâ€“Bâ€“Câ€“N materials: <i>Ab initio</i> calculations and experimental verification. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2007, 25, 1411-1416. | 0.9 | 21 |
| 70 | Hard multifunctional Hfâ€“Bâ€“Siâ€“C films prepared by pulsed magnetron sputtering. Surface and Coatings Technology, 2014, 257, 301-307. | 2.2 | 20 |
| 71 | Effect of the Si content on the microstructure of hard, multifunctional Hfâ€“Bâ€“Siâ€“C films prepared by pulsed magnetron sputtering. Applied Surface Science, 2015, 357, 1343-1354. | 3.1 | 20 |
| 72 | Thermal, mechanical and electrical properties of hard B4C, BCN, ZrBC and ZrBCN ceramics. Ceramics International, 2016, 42, 4361-4369. | 2.3 | 20 |

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| 73 | The effect of argon on the structure of amorphous SiBCN materials: an experimental andab initiostudy. Journal of Physics Condensed Matter, 2006, 18, 2337-2348. | 0.7 | 19 |
| 74 | Transport and ionization of sputtered atoms in high-power impulse magnetron sputtering discharges. Journal Physics D: Applied Physics, 2013, 46, 105203. | 1.3 | 19 |
| 75 | The depth profile analysis of W-Si-N coatings after thermal annealing. Surface and Coatings Technology, 2002, 161, 111-119. | 2.2 | 18 |
| 76 | Plasma nitriding combined with a hollow cathode discharge sputtering at high pressures. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1997, 15, 2636-2643. | 0.9 | 17 |
| 77 | Magnetron sputtering of alloy-based films and its specifity. European Physical Journal D, 1998, 48, 1209-1224. | 0.4 | 17 |
| 78 | Effect of implanted argon on hardness of novel magnetron sputtered Siâ€"Bâ€"Câ€"N materials: experiments andab initiosimulations. Journal of Physics Condensed Matter, 2007, 19, 196228. | 0.7 | 17 |
| 79 | Thermal conductivity of high-temperature Siâ€"Bâ€"Câ€"N thin films. Surface and Coatings Technology, 2011, 206, 2030-2033. | 2.2 | 17 |
| 80 | Magnesium as a representative analyte metal in argon inductively coupled plasmas. I. An extensive collisional-radiative model. Spectrochimica Acta, Part B: Atomic Spectroscopy, 1997, 52, 599-608. | 1.5 | 16 |
| 81 | Magnesium as a representative analyte metal in argon inductively coupled plasmas. II. Population mechanisms in analytical zones of different spectrochemical systems. Spectrochimica Acta, Part B: Atomic Spectroscopy, 1997, 52, 609-619. | 1.5 | 15 |
| 82 | Optical emission spectra and ion energy distribution functions in TiN deposition process by reactive pulsed magnetron sputtering. Surface and Coatings Technology, 2005, 200, 835-840. | 2.2 | 15 |
| 83 | Production of Ti films with controlled texture. Surface and Coatings Technology, 1995, 76-77, 274-279. | 2.2 | 14 |
| 84 | Planar magnetron with additional plasma confinement. Vacuum, 1995, 46, 341-347. | 1.6 | 14 |
| 85 | Microwave plasma nitriding of a low-alloy steel. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 2715-2721. | 0.9 | 14 |
| 86 | Effect of N and Zr content on structure, electronic structure and properties of ZrBCN materials: An ab-initio study. Thin Solid Films, 2013, 542, 225-231. | 0.8 | 14 |
| 87 | Dependence of characteristics of MSiBCN (M = Ti, Zr, Hf) on the choice of metal element: Experimental and ab-initio study. Thin Solid Films, 2016, 616, 359-365. | 0.8 | 14 |
| 88 | Optical emission spectroscopy during the deposition of zirconium dioxide films by controlled reactive high-power impulse magnetron sputtering. Journal of Applied Physics, 2017, 121, . | 1.1 | 14 |
| 89 | Magnetron sputtered Hfâ€"Bâ€"Siâ€"Câ€"N films with controlled electrical conductivity and optical transparency, and with ultrahigh oxidation resistance. Thin Solid Films, 2018, 653, 333-340. | 0.8 | 14 |
| 90 | Thermal annealing of sputtered Alâ€"Siâ€"Cuâ€"N films. Vacuum, 2003, 72, 21-28. | 1.6 | 13 |

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| 91 | Synthesis of TiO2 photocatalyst and study on their improvement technology of photocatalytic activity. Surface and Coatings Technology, 2005, 200, 534-538. | 2.2 | 13 |
| 92 | Enhancement of the deposition rate in reactive mid-frequency ac magnetron sputtering of hard and optically transparent ZrO 2 films. Surface and Coatings Technology, 2018, 336, 54-60. | 2.2 | 12 |
| 93 | Collisional-radiative ionization and recombination in an inductively coupled argon plasma. Spectrochimica Acta, Part B: Atomic Spectroscopy, 1992, 47, 681-688. | 1.5 | 11 |
| 94 | Surface morphology of sputter deposited low melting point metallic thin films. European Physical Journal D, 1994, 44, 565-574. | 0.4 | 11 |
| 95 | Anodic plasma nitriding with a molybdenum cathode. Vacuum, 1995, 46, 43-47. | 1.6 | 11 |
| 96 | Microstructure evolution in amorphous Hf-B-Si-C-N high temperature resistant coatings after annealing to 1500 Â°C in air. Scientific Reports, 2019, 9, 3603. | 1.6 | 11 |
| 97 | Pulsed Magnetron Sputtering of Strongly Thermochromic VO2-Based Coatings with a Transition Temperature of 22 Â°C onto Ultrathin Flexible Glass. Coatings, 2020, 10, 1258. | 1.2 | 11 |
| 98 | Ion Flux Characteristics in Pulsed Dual Magnetron Discharges Used for Deposition of Photoactive TiO<sub>2</sub> Films. Plasma Processes and Polymers, 2011, 8, 191-199. | 1.6 | 10 |
| 99 | Dependence of structure and properties of hard nanocrystalline conductive films MBCN (M = Ti, Zr,) Tj ETQq1 1 0.784314 rgBT /Overlo | 0.8 | 10 |
| 100 | Ion-flux characteristics during low-temperature (300 Â°C) deposition of thermochromic VO<sub>2</sub> films using controlled reactive HiPIMS. Journal Physics D: Applied Physics, 2019, 52, 025205. | 1.3 | 10 |
| 101 | Transfer of the sputter technique for deposition of strongly thermochromic VO2-based coatings on ultrathin flexible glass to large-scale roll-to-roll device. Surface and Coatings Technology, 2022, 442, 128273. | 2.2 | 10 |
| 102 | Electron energy distribution function in the collisional-radiative model of an argon plasma. Journal Physics D: Applied Physics, 1985, 18, 347-358. | 1.3 | 9 |
| 103 | Seebeck effect in polycrystalline semiconductors. Thin Solid Films, 1982, 92, 259-271. | 0.8 | 8 |
| 104 | Magnetron with gas injection through hollow cathodes machined in sputtered target. Surface and Coatings Technology, 2001, 148, 296-304. | 2.2 | 8 |
| 105 | Dynamics of processes during the deposition of ZrO2 films by controlled reactive high-power impulse magnetron sputtering: A modelling study. Journal of Applied Physics, 2017, 122, 043304. | 1.1 | 8 |
| 106 | Reactive high-power impulse magnetron sputtering of ZrO2 films with gradient ZrOx interlayers on pretreated steel substrates. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 031503. | 0.9 | 7 |
| 107 | Study of the high-temperature oxidation resistance mechanism of magnetron sputtered Hf7B23Si17C4N45 film. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, . | 0.9 | 7 |
| 108 | Effect of energetic particles on pulsed magnetron sputtering of hard nanocrystalline MBCN (Mâ€¯=â€¯Ti, Zr,) Tj ETQq0 0 0 rgBT /Overloc | 0.8 | 7 |

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| 109 | Dependence of characteristics of Hf(M)SiBCN (MÂ=ÂY, Ho, Ta, Mo) thin films on the M choice: Ab-initio and experimental study. Acta Materialia, 2021, 206, 116628. | 3.8 | 7 |
| 110 | Microstructure of high-performance thermochromic ZrO2/V0.984W0.016O2/ZrO2 coating with a low transition temperature (22ÂÂ°C) prepared on flexible glass. Surface and Coatings Technology, 2021, 424, 127654. | 2.2 | 7 |
| 111 | Ion-bombardment characteristics during deposition of TiN films using a grid-assisted magnetron system with enhanced plasma potential. Vacuum, 2007, 81, 1109-1113. | 1.6 | 6 |
| 112 | Effect of ion bombarding energies on photocatalytic TiO2 films growing in a pulsed dual magnetron discharge. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2011, 29, . | 0.9 | 6 |
| 113 | Effect of voltage pulse characteristics on high-power impulse magnetron sputtering of copper. Plasma Sources Science and Technology, 2013, 22, 015009. | 1.3 | 6 |
| 114 | Depth profile analysis of minor elements by GD-OES: Applications to diffusion phenomena. Fresenius' Journal of Analytical Chemistry, 1996, 354, 188-192. | 1.5 | 5 |
| 115 | New approach to understanding the reactive magnetron sputtering of hard carbon nitride films. Diamond and Related Materials, 2000, 9, 582-586. | 1.8 | 5 |
| 116 | Thermal stability of structure, microstructure and enhanced properties of Zrâ€“Taâ€“O films with a low and high Ta content. Surface and Coatings Technology, 2018, 335, 95-103. | 2.2 | 5 |
| 117 | Tunable composition and properties of Al-O-N films prepared by reactive deep oscillation magnetron sputtering. Surface and Coatings Technology, 2020, 392, 125716. | 2.2 | 5 |
| 118 | Extraordinary high-temperature behavior of electrically conductive Hf7B23Si22C6N40 ceramic film. Surface and Coatings Technology, 2020, 391, 125686. | 2.2 | 5 |
| 119 | Excited level populations of argon atoms in a non-isothermal plasma. Journal Physics D: Applied Physics, 1986, 19, 1879-1888. | 1.3 | 4 |
| 120 | Mutual interdiffusion of elements in steel and Ti coating and aluminium and Ti coating couples during plasma nitriding. Surface and Coatings Technology, 1995, 74-75, 609-613. | 2.2 | 4 |
| 121 | Enhancement of high-temperature oxidation resistance and thermal stability of hard and optically transparent Hfâ€“Bâ€“Siâ€“Câ€“N films by Y or Ho addition. Journal of Non-Crystalline Solids, 2021, 553, 120470. | 1.5 | 3 |
| 122 | Coronal and Collisional â€” Radiative Model of the Plasma for the Case of Hydrogen Glow Discharge. Beitrage Aus Der Plasmaphysik, 1983, 23, 373-379. | 0.1 | 2 |
| 123 | Interdiffusion between Ti and steel elements in Ti coating/steel substrate couple. Vacuum, 1996, 47, 871-877. | 1.6 | 2 |
| 124 | Microstructure of High Temperature Oxidation Resistant Hf6B10Si31C2N50 and Hf7B10Si32C2N44 Films. Coatings, 2020, 10, 1170. | 1.2 | 2 |
| 125 | Phase transformation in sputtered Tiâ€“SS alloy film during plasma nitriding. Thin Solid Films, 1998, 317, 458-462. | 0.8 | 1 |
| 126 | Fundamentals of elementary processes in plasmas. Surface and Coatings Technology, 1998, 98, 1557-1564. | 2.2 | 1 |

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| 127 | Effective nitriding of steels outside low-pressure microwave discharges. Surface and Coatings Technology, 2002, 156, 182-184. | 2.2 | 1 |
| 128 | Comment on two new collisional-radiative models for an argon plasma. Journal of Quantitative Spectroscopy and Radiative Transfer, 1992, 47, 431-432. | 1.1 | 0 |
| 129 | Effects of power per pulse on reactive HiPIMS deposition of ZrO2 films: A time-resolved optical emission spectroscopy study. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, 061305. | 0.9 | 0 |
| 130 | Multifunctional MoOx and MoOxNy films with 2.5 < x < 3.0 and y < 0.2 prepared using controlled reactive deep oscillation magnetron sputtering. Thin Solid Films, 2021, 717, 138442. | 0.8 | 0 |